

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	59238	(implanting implantation implant\$3) with (wafer substrate)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/03/03 15:31
L3	1194	2 and (implanting implantation implant\$3) near5 rate	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/03/03 15:30
L4	92	3 and (wafer substrate) near5 pressure	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/03/03 15:32